

L Number	Hits	Search Text	DB	Time stamp
11	2534	(relief hole) with determining	USPAT	2002/01/08 11:38
12	442	determining near2 wear	USPAT	2002/01/08 11:38
13	1210	(monitoring measuring determining) near2 wear	USPAT	2002/01/08 11:39
14	2403	polishing adj pad	USPAT	2002/01/08 11:40
16	1	((monitoring measuring determining) near2 wear) and ((polishing adj pad) with (relief hole grid))	USPAT	2002/01/08 11:40
15	77	(polishing adj pad) with (relief hole grid)	USPAT	2002/01/08 11:41
-	2395	polishing adj pad	USPAT	2002/01/07 17:10
-	1725	(polishing adj pad) and (CMP (chemical adj mechanical adj polishing))	USPAT	2002/01/07 17:12
-	546	pad adj wear	USPAT	2002/01/07 17:12
-	15	(pad adj wear) WITH (monitoring measuring)	USPAT	2002/01/07 17:16
-	59	((polishing adj pad) and (CMP (chemical adj mechanical adj polishing))) and (pad adj wear)	USPAT	2002/01/07 17:16